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United States Patent [19]

Chau et al.

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[54] TRANSISTOR WITH LOW RESISTANCE TIP AND METHOD OF FABRICATION IN A CMOS PROCESS

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[*] Notice: This patent issued on a continued prosecution application filed under 37 CFR 1.53(d), and is subject to the twenty year patent term provisions of 35 U.S.C.

154(a)(2).

[21] Appl. No.: **08/581,243**

[22] Filed: Dec. 29, 1995

Related U.S. Application Data

[63] Continuation-in-part of application No. 08/363,749, Dec. 23, 1994, Pat. No. 5,710,450.

[51]	Int.	CL^7	 H01L	21/8238
21	III t.	CI.	 HULL	21/0230

FOR 180, FOR 197, FOR 216, FOR 217, FOR 218, FOR 251, FOR 250, FOR 219, 148/DIG. 147, DIG. 19, DIG. 59; 257/288,

[56] References Cited

U.S. PATENT DOCUMENTS

4,133,704	1/1979	MacIver et al 148/1.5
4,683,645	8/1987	Naguib et al 437/41
4,876,213	10/1989	Pfiester 437/34
4,998,150	3/1991	Rodder et al 357/23.1
5,006,476	4/1991	De Jong et al 437/31

5,162,263	11/1992	Kunishima et al 437/200
5,168,072	12/1992	Moslehi 437/41
5,231,042	7/1993	Ilderem et al 437/44
5,285,088	2/1994	Sato et al
5,336,903	8/1994	Ozturk et al 257/19
5,341,014	8/1994	Fujii et al 257/377
5,352,631	10/1994	Sitaram et al 437/200
5,393,685	2/1995	Yoo et al 437/44
5,397,909	3/1995	Moslehi 257/383
5,405,795	4/1995	Beyer et al 437/89

(List continued on next page.)

FOREIGN PATENT DOCUMENTS

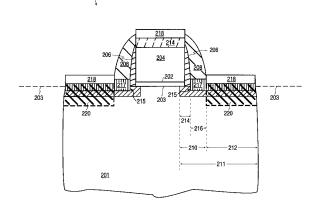
8448061	5/1998	European Pat. Off	
361051959	3/1986	Japan 438/FOR 1	68

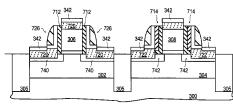
Primary Examiner—Long Pham Attorney, Agent, or Firm—Blakely, Sokoloff, Taylor & Zafman LLP

[57] ABSTRACT

A novel transistor with a low resistance ultra shallow tip region and its method of fabrication in a complementary metal oxide semiconductor (CMOS) process. According to the preferred method of the present invention, a first gate dielectric and a first gate electrode are formed on a first portion of a semiconductor substrate having a first conductivity type, and a second gate dielectric and a said gate electrode are formed on a second portion of semiconductor substrate having a second conductivity type. A silicon nitride layer is formed over the first portion of the semiconductor substrate including the first gate electrode and over the second portion of the semiconductor substrate including the second gate electrode. The silicon nitride layer is removed from the second portion of the silicon substrate and from the top of the second gate electrode to thereby form a first pair of silicon nitride spacers adjacent to opposite sides of the second gate electrode. A pair of recesses are then formed in the second portion of the semiconductor substrate in alignment with the first pair of sidewall spacers. A selectively deposited semiconductor material is then formed in the recesses.

52 Claims, 13 Drawing Sheets







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U.S. PATENT DOCUMENTS	5,620,912	4/1997	Hwang et al	438/301
5,478,776 12/1995 Luftman et al	5,710,450	1/1998	Chau et al	257/344
5,538,909 7/1996 Hsu	5,726,071	3/1998	Segawa et al	437/57
5.569.624 10/1996 Weiner	5,770,507	6/1998	Chen et al	438/305



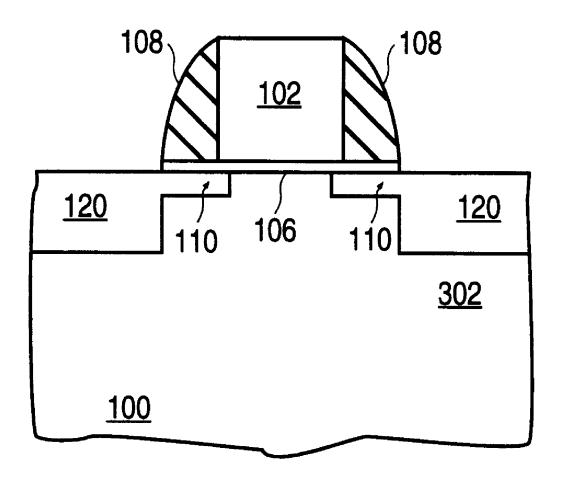
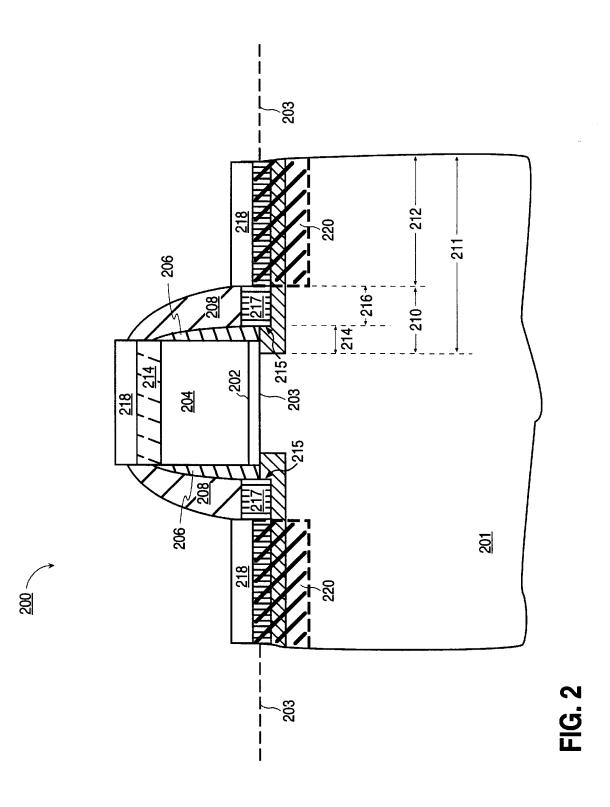


FIG. 1 (PRIOR ART)





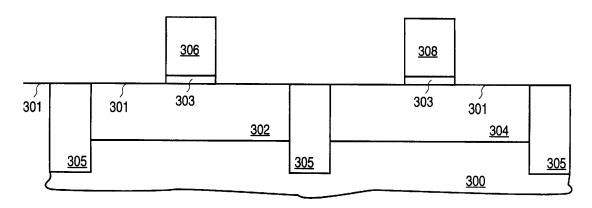


FIG. 3A

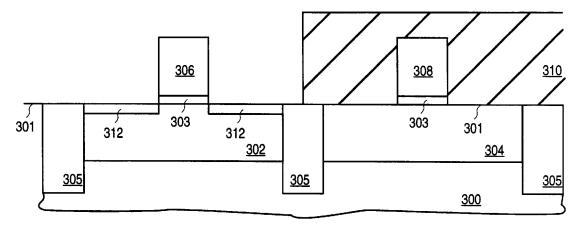


FIG. 3B

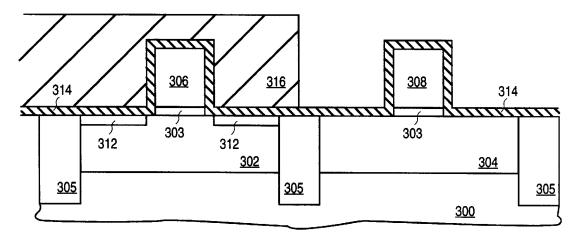


FIG. 3C

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